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Improving Carrier Lifetime of Tin Sulfide via Prediction and Mitigation of Harmful Point Defects

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Tin monosulfide (SnS) is an emerging thin-film absorber material for photovoltaics. An outstanding challenge is to improve carrier lifetimes to >1 ns, which should enable >10% device efficiencies. However, reported results to date have only demonstrated lifetimes at or below 100 ps. In this study, we employ defect modeling to identify the sulfur vacancy and defects from Fe, Co, and Mo as most recombination-active. We attempt to minimize these defects in crystalline samples through high-purity, sulfur-rich growth and experimentally improve lifetimes to >3 ns – thus achieving our 1 ns goal. This framework may prove effective for unlocking the lifetime potential in other emerging thin film materials by rapidly identifying and mitigating lifetime-limiting point defects.

Photovoltaics, thin films, earth-abundant, defects, carrier lifetime
Inorganic thin-film absorbers for photovoltaics (PVs) have struggled to achieve large-scale market penetration; thin film technology constituted less than 7% of 2015 PV energy production\(^1\). At the same time, technological improvements over current state-of-the-art silicon cells on the market will be necessary to meet cost and climate goals\(^2,3\). Thin films represent a potential low-cost path to scalable PV. However, the majority of emerging thin film absorbers still underperform in efficiency despite promising optical properties\(^4\), a problem which in many cases can be linked to a short minority-carrier lifetime\(^5\).

Impurity management has been critical to achieving long lifetimes in other materials. Significant improvements in silicon technology were due to understanding the dependence of carrier lifetime on iron\(^6-10\) and other metal impurities\(^11\) that cause deep carrier traps. Certain metal impurities have also been shown to form performance-limiting deep trap states in some thin film semiconductors\(^12-14\).

Controlling vacancies, and intrinsic defects in general, has also proven critical to improving performance, particularly for thin-film PV absorbers. Modeling the complex intrinsic point-defect profiles of Cu(In,Ga)Se\(_2\) (CIGS)\(^15,16\) and Cu\(_2\)ZnSnS\(_4\) (CZTS)\(^17,18\), for instance, has informed growth parameters to achieve high (>1 ns) lifetimes.

We used tin monosulfide (SnS) as a test case material; while SnS shows promise as an intrinsically \(p\)-type, earth-abundant and nontoxic material with strong optical properties for PV\(^19\), it is limited by as-of-yet insufficient minority-carrier (electron) lifetimes of <100 ps\(^5\). Improving electron lifetimes to >1 ns is predicted to enable device efficiency increases from the current record of 4.4\%\(^19\) to >10%\(^20\). Prior work implicates intragranular point defects as limiting carrier transport\(^21-23\).
In this work, we applied a combined modeling and experimental framework to point defect management in SnS, and predict that carrier lifetime depends strongly on the sulfur vacancy defect as well as substitutional defects caused by Fe, Co, and Mo. We independently demonstrate the importance of sulfur content as well as impurity content on lifetime in SnS samples. Moreover, through targeted defect management we achieve – for the first time to our knowledge – SnS minority-carrier lifetimes in excess of 1 ns. This constitutes approximately a two order-of-magnitude increase over previously reported results\(^5\) for thin films, and opens a path to SnS devices with efficiencies >10%. We believe this represents a generalizable path to managing lifetime-limiting defects in novel absorber materials to accelerate future development.

We used Shockley-Read-Hall (SRH) statistics\(^{24-26}\), informed by density function theory (DFT) calculations of defect energetics, to predict the defect-limited lifetime for all possible intrinsic vacancies, substitutionals, and interstitials, as well as extrinsic point defects caused by any impurities known to be in the material feedstock or growth and processing environments. As shown in Figure 1a, \(V_{S}\), \(Mo_{Sn}\), \(Fe_{Sn}\), and \(Co_{Sn}\) were predicted to have over a two order-of-magnitude more severe effect on carrier lifetime at a given concentration compared to other defects calculated herein. Those defects calculated to have a relatively benign effect on carrier lifetime (such as \(V_{Sn}\), \(Na_{Sn}\), and \(Sb_{Sn}\)) due to shallow states, as well as defects with extremely high formation energy (such as \(S_{Sn}\) or \(Sn_{S}\)) were excluded from Figure 1a. For details on the DFT and SRH calculations, including relevant assumptions, please refer to the methods.

Defect formation energy curves for the four key defects (as well as the benign acceptor \(V_{Sn}\)) are shown in Figure 1b. Defect energy levels, corresponding to charge state transitions, are denoted by circles. Trap levels for the calculated defects show reasonable agreement with previous calculations for defects in SnS\(^{27,28}\), with the exception of the \(V_{Sn}\) defect, which is
predicted here to be within the valence band. We see that all four of these key defects show one or more relatively deep trap levels, and are all positively charged in $p$-type material, thus attracting minority carriers (electrons). These findings suggest that increasing the chemical activity of sulfur, and decreasing that of Fe, Co, and Mo, will lead to significant lifetime improvements in SnS.

Figure 1. a) Defect-limited lifetimes for likely point defects in SnS. Four defects (intrinsic $V_{Sn}$ as well as extrinsic $Mo_{Sn}$, $Fe_{Sn}$, and $Co_{Sn}$ in solid lines) are predicted to be most detrimental to lifetime. b) Formation energy vs. Fermi energy for the lowest-energy charge state of these four defects as well as the tin vacancy ($V_{Sn}$), which acts as a shallow acceptor. Circles represent transitions in charge state, and thus trap levels of each defect. Calculations were performed under sulfur-rich conditions ($\mu_s = 0$ eV, $\mu_{Sn} = -1.05$ eV).

Consistent with the defect calculations above, we observed lifetime increases as we independently increased sulfur content and feedstock purity in SnS crystal samples. Figure 2a compares samples with constant purity but varying sulfur content, while Figure 2b compares
samples of varying purity with sulfur content kept constant. For all samples we estimated carrier lifetimes by fitting time-resolved photoluminescence (TRPL) measurements with biexponential decay functions. Photoluminescence (PL) spectra (Figure 2c) were analyzed to inform optical filter choices for TRPL measurements; spectra for all samples showed dominant emission at 1.3 and 1.78 eV, in agreement with previous optical transition levels reported in the literature\textsuperscript{29-31}. A higher-energy shoulder was also seen just above 2 eV, and was particularly pronounced in the sulfur-poor samples.

**Figure 2.** Electro-optical measurements of SnS. **a)** TRPL measurements showing longer decay time constants (and by proxy carrier lifetimes) with increased atomic purity. **b)** TRPL measurements showing that for samples with high atomic purity, increasing sulfur content further lengthens carrier lifetime. **c)** Spectral photoluminescence profiles, showing dominant peaks at
1.3 and 1.78 eV. d) Lifetime improvements with increasing sulfur content correlate with an increase in carrier concentration, which can be linked to lower sulfur vacancy concentration.

We observed lifetime increases as we increased purity and sulfur content. Moving from 99.99%-pure (4N) to 99.9999%-pure (6N) feedstock (with over two-order-of-magnitude decreases in key metal content) generated an increase in the fast biexponential decay time constant \( \tau_1 \) from at or below the instrument response function (IRF) to over 400 ps, as well as a nearly 50% increase in the slower decay constant \( \tau_2 \). The 4N sample showed the shortest decay constants of all samples (even the sulfur-poor samples, which were grown from higher-purity feedstock). This suggests that adequate purity standards (for SnS, this means Fe, Co, and Mo concentrations in the ppb range or lower) are a prerequisite to achieving long carrier lifetimes in SnS.

In samples made from 6N Sn and 5.5N S, increasing the sulfur-to-tin ratio led to further increases in \( \tau_1 \) from near the instrument response function to over 1.6 ns. Note that while the Very S-Rich sample has biexponential character, the fit is dominated by the long decay and appears nearly monoexponential. \( \tau_2 \) increased slightly but is high (>3 ns) for all samples. In agreement with our defect modeling, the highest-performing sample was the Very S-Rich sample, which had the highest sulfur content during growth and was made from high-purity (6N Sn and 5.5N S) feedstocks.

It is as yet unclear why all samples exhibit quite long (>2 ns) values of \( \tau_2 \) but show large differences in \( \tau_1 \). In polycrystalline thin films as well as single crystals\(^{32}\), short- and long-time components of TRPL data have been attributed to surface and bulk lifetimes, respectively. Stoichiometry can affect surface quality, and cation vacancy segregation to surfaces during
growth is thought to have a large effect in polycrystalline CIGS. However, such a mechanism is unlikely in this instance because we exfoliate a surface layer of each sample prior to measurement to expose bulk material. Further work – potentially employing depth-resolved TRPL – is needed to better understand the different recombination pathways in our material.

In order to correlate the improvements in lifetime shown above with reductions in defect density, it is critical to understand relative sulfur vacancy (as well as impurity) concentrations in the SnS samples. We estimate sulfur vacancy content using carrier concentrations extracted from Hall Effect measurements. We assume identical thermal treatment for all samples, low concentrations of extrinsic dopants (as evidenced from impurity measurements, discussed below) and intrinsic interstitial and antisite defects (as evidenced by DFT calculations). Then, in accordance with Kröger-Vink defect chemistry theory for a II-VI binary semiconductor, we can say that the carrier concentration $p$ and the sulfur vacancy content $[V_S]$ are inversely related. As shown in Figure 2d, we observe a nearly 4 order-of-magnitude increase in $p$ between the Very S-Poor and Very S-rich growth conditions, suggesting a commensurate reduction in $[V_S]$. Note that we see a plateau in carrier concentration between the S-Rich and Very S-Rich samples, possibly due to the formation of sulfurous phase impurities at the surface, which would pin the sulfur chemical potential during growth and result in similar $V_{Sn}$ (and thus hole) concentrations in both samples.

The increase in PL decay constants with increasing sulfur content correlated with carrier concentration increases (Fig. 2d), which we associate with decreases in $[V_S]$. Based on our defect calculations in Figure 1a, we expect a two order-of-magnitude change in defect-limited electron lifetimes for every one order-of-magnitude change in $[V_S]$. We do not see such a drastic increase in either decay constant, though $\tau_1$ improved by approximately one order of magnitude between
the “Very S-poor” and “Very S-rich” samples. $\tau_2$ increased slightly as well. This suggests that under these growth conditions, recombination may not be completely dominated by $V_S$.

However, the ability to increase carrier lifetime to well over 1 ns in SnS by altering sulfur and metal impurity content provides us with powerful handles with which to optimize SnS material quality.

To better understand changes in impurity-related defect concentrations, we monitor concentrations of Fe, Mo, and Co — predicted to have the largest impact on carrier lifetime in SnS — using time-of-flight secondary ion mass spectrometry (ToF-SIMS). All samples showed these metals near or below the detection limit, and thus we can only say that these metals are likely at or below several ppm in all samples. We also detect low concentrations of alkali metals and other common dopants, suggesting that our Hall measurements above are likely dominated by intrinsic defects. For further intuition on relative impurity levels, we refer to the feedstock impurity analysis performed by the manufacturer presented in Table 1. For complete SIMS datasets for all samples, see S.I.

**Table 1.** Atomic concentrations (in ppb) of Fe, Co, and Mo for all feedstocks used in this study.

<table>
<thead>
<tr>
<th>Feedstock</th>
<th>6N-pure Sn</th>
<th>5.5N-pure S</th>
<th>4N-pure SnS</th>
</tr>
</thead>
<tbody>
<tr>
<td>Supplier</td>
<td>Alfa Aesar</td>
<td>Alfa Aesar</td>
<td>Sigma Aldrich</td>
</tr>
<tr>
<td>Measurement</td>
<td>GDMS</td>
<td>GDMS</td>
<td>ICP-MS</td>
</tr>
<tr>
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<td>50</td>
<td>1000</td>
</tr>
<tr>
<td>Fe</td>
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</tr>
<tr>
<td>Mo</td>
<td>&lt;1</td>
<td>&lt;1</td>
<td>&lt;1</td>
</tr>
</tbody>
</table>
To ensure that all measurements were performed on phase-pure SnS, we performed X-ray diffraction (XRD) and Raman spectroscopy measurements. XRD patterns (Figure 3a) confirmed that the crystallite interior for all samples was phase-pure SnS, with all detected peaks matching literature XRD patterns for orthorhombic SnS (space group \textit{Pnma}).

Raman spectroscopy (Figure 3b) performed on the crystal surfaces and in the bulk revealed that in some of the samples, particularly the sulfur-rich ones, phase impurities were present at the surface of the crystals. However, once a surface layer was exfoliated (thus exposing a pristine interior layer) no further phase impurities were detected.

**Figure 3.** Structural characterization of crystal samples. \textbf{a)} XRD patterns indicate phase-pure SnS for all samples. \textbf{b)} Raman spectroscopy performed on crystal surfaces (beige curves) showed phase impurities (peak at \(~310\text{ cm}^{-1}\), indicated by black curve) for some samples, which was no longer evident after exfoliation and removal of the surface layer (color-coded curves).

To understand the potential impact of our observed carrier lifetime improvements on devices, we perform SCAPS-1D\textsuperscript{35} device simulations to predict device efficiencies assuming realistic device architecture\textsuperscript{36} and accounting for parasitic absorption losses. Figure 4 shows calculated iso-efficiency contours as a function of the SnS absorber layer’s minority-carrier lifetime and majority carrier concentration. Experimental values are overlaid for previously
reported thin films\textsuperscript{5} as well as the 4N and Very S-Rich samples. We predict that the material quality achieved for the Very S-Rich sample is sufficient to achieve \textgreater 10\% efficient devices. For more information regarding device calculations refer to the methods.

\textbf{Figure 4.} Contour plot of SCAPS-1D device simulations relating efficiency of a realistic SnS device to the SnS minority-carrier lifetime and majority carrier concentration. Experimental data from previously reported thin films as well as the 4N and Very S-Rich samples are overlaid. For the latter two samples, values of $\tau_1$ and $\tau_2$ are both presented.

Several of the methods applied here to SnS should be generalizable to other thin-film materials. Using defect modeling to identify minimum purity requirements and optimal growth stoichiometry can help minimize harmful intrinsic and extrinsic point defects. Primary focus should be placed on impurities known to be present in the material feedstock (certificates of analysis are typically available upon purchase for any commercial feedstock), as well as all
processing equipment. High-purity feedstocks can either be purchased or, in the case of molecular materials, synthesized in lab via reaction of high-purity elemental precursors in a high-purity environment. As well, anion overpressure is often a best-practice for chalcogenide materials systems\textsuperscript{37}.

In this study we significantly improved carrier lifetime in SnS through defect management guided by theoretical predictions. Moreover, we demonstrated the ability to span the range from \textit{a priori} defect calculations to experimental lifetime improvements in an emerging thin-film material.

In conclusion, we predicted that four defects are particularly detrimental to carrier lifetime in SnS – the intrinsic vacancy $V_S$ and the extrinsic substitutionals $Co_{Sn}$, $Fe_{Sn}$, and $Mo_{Sn}$. Separately, we demonstrated experimentally that both increasing sulfur content and reducing impurity concentration result in significant improvements in minority-carrier lifetime. Our device simulations suggest that these observed long lifetimes, when achieved in thin-film form, may enable SnS devices with efficiencies >10\%. Moreover, we hope that a similar approach can accelerate improvements in other emerging materials.

Vienna \textit{ab initio} Simulation Package\textsuperscript{38,39} was used for density functional theory (DFT) defect calculations with the exchange-correlation functional of Perdew-Burke-Ernzerhof\textsuperscript{40}, generalized gradient approximation, and projector augmented-wave (PAW)\textsuperscript{41,42} pseudopotentials. Additionally the Heyd-Scuseria-Ernzerhof hybrid functional\textsuperscript{43,44} was employed with an exchange coefficient of 0.1 to accurately calculate the indirect band gap of 1.1 eV for SnS\textsuperscript{45}. For defect calculations, we use a 72-atom supercell (3x3x3) with a 2x2x2 grid of k-points. Calculations account for spin polarization, but not spin orbit coupling due to calculation cost. Calculations
were performed assuming a sulfur-rich environment, with the chemical potential of sulfur set to zero, and that of Sn at -1.05 eV (the formation enthalpy of SnS). Note that going to S-poor conditions would exhibit a shift in formation energy (specifically, a decrease for V$_s$ and increase for V$_{Sn}$) but not in trap levels. For more detail regarding the defects calculation methodology and assumptions regarding chemical potentials, as well as prior examples of similar calculations, see references 46-48.

Vacancies as well as all impurities known to be in the SnS, Sn, or S feedstocks, or in any materials used during processing such as the quartz amouples, were included in calculations. Intrinsic antisites and interstitials were found to have very high formation energy from DFT and were excluded from SRH calculations.

The calculated defect charge transition levels were input into an SRH statistical model to calculate defect-limited lifetime (i.e. the material lifetime assuming recombination only through a given defect) as a function of that defect’s concentration according to the relations laid out in 24. Capture cross-sections were estimated assuming a purely Coulombic model, which has been shown to approximate capture cross sections in established materials to within an order of magnitude 49. Multivalent states were simplified into multiple single-level SRH-like defects according to established guidelines 50. Material parameters are estimated based on prior literature – hole concentration of 10$^{16}$ cm$^{-3}$ 23 with an assumed 10% compensation, relative permittivity of 37.3 51, and effective masses $m_h = 3m_e = 1.5m_o$ 28. Because of the assumptions stated above, results should be treated as qualitative.

Device simulations were performed using SCAPS-1D software 35, the results of which were batched and analyzed in MATLAB to produce contour plots of device efficiency vs. absorber layer minority-carrier lifetime and majority-carrier concentration. Material and device
parameters for a “present day” device, including realistic parasitic absorption losses, can be found in\textsuperscript{36}.

Two sets of SnS crystal samples were grown from the melt to separately evaluate the effects of sulfur content as well as impurity content.

For the first set, crystals were grown using molecular SnS feedstock at two different impurity levels—99.99\% (4N) and 99.9999\% (6N). 4N SnS was obtained from Sigma Aldrich. 6N SnS, not available commercially, was synthesized in-house from 6N-pure Sn from Alfa Aesar and 4\% H\textsubscript{2}S gas in N\textsubscript{2} balance with negligible metal content by heating Sn in a tube furnace for several hours at 600\degreeC with 100 sccm H\textsubscript{2}S flow.

For the second set, sulfur content was varied. All crystals were synthesized from elemental 6N-pure Sn and 5.5N-pure S, both from Alfa Aesar. Crystals were grown with Sn/S ratios of 48/52 (“Very Sulfur-Rich”), 49/51 (“Sulfur-Rich”), 51/49 (“Sulfur-Poor”), and 52/48 (“Very Sulfur-Poor”).

Regardless of feedstock, all crystals were grown in ampoules of 4.5N-pure quartz sealed under 2 Torr of Ar, heated to 950\degreeC over 2 hours, held at 950\degreeC for 12 hours, and cooled to room temperature over 5 days at 0.125\degreeC/min.

Samples were cut from crystals and mounted with the basal (100) plane parallel to glass substrates. SnS has a layered orthorhombic structure, and it is possible to exfoliate layers along the (100) plane using tape. Unless otherwise stated, all samples were exfoliated in this way before measurements were performed. This exposes a pristine layer within the crystal bulk and ensures that all measurements are performed on phase-pure SnS.

Spectral photoluminescence (PL) and Raman spectroscopy measurements were both performed under ambient conditions on a Horiba LabRam multiline Raman/PL
Spectrophotometer using a 532 nm laser operating at 2 mW, focused on a ~500 nm diameter Gaussian spot with a 50x confocal microscope objective. Total exposure time was ~30 s (Raman) and ~15 min (PL). Samples were visually inspected before and after measurements and repeat measurements were performed at the same location to ensure repeatability.

X-ray diffraction (XRD) was performed on a Bruker D8 X-ray diffractometer with a General Area Detector Diffraction System employing Cu Kα radiation. Samples were prepared as powders according to best practices.

Time-of-flight secondary ion mass spectrometry (ToF-SIMS) impurity analysis was performed on an ION ToF-SIMS 4 using Bi⁺ as primary ions. Profiles were performed using 2 keV O₂ (positive polarity) and Cs (negative polarity) primary ions.

Lifetime data was collected under ambient conditions without background illumination using a time-correlated single photon counting (TCSPC) system using a PicoQuant LDH-P-FA530B 532 nm picosecond laser. Samples were illuminated under 50±1 µW illumination on a ~180-µm-diameter spot with a 10 MHz repetition rate, corresponding to a fluence of ~4.9 nJ/(cm²·pulse). PL emission was collected using a Micro Photon Devices, SPD-100-C0C single-photon-sensitive avalanche photodiode. The collected radiation was filtered through a 532 nm notch filter, 800 nm short pass filter, and 550 nm longpass filter.

Hall Effect measurements were performed using a Keithley 4200 semiconductor characterization system. Samples were prepared in the Van der Pauw configuration with 200-nm-thick 0.1x0.1mm gold contacts on top of a 20 nm Ti adhesion layer. Data was taken under magnetic fields between ±1.5 Tesla in 0.1 T increments.

The authors declare no competing financial interest.
Supporting Information: Additional DFT defect and band structure / density-of-states calculations for SnS, SIMS scans for all samples, X-ray photoemission spectroscopy analysis of Sn chemical state in all samples.

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